

IN THE CLAIMS

Please amend the claims as follows:

Claims 1-43 (Canceled).

Claim 44 (Currently Amended): A vacuum processing apparatus, comprising:  
a processing chamber, including

a lower wall;

an upper wall;

a side wall coupled to the lower wall and the upper wall; and

a plurality of pumping ports, formed in one of the lower wall, the upper wall,  
or the side wall;

~~at least one~~ a pumping cell, integrally including a vacuum pump and a valve, coupled  
to a first pumping port; and

~~at least one~~ a seal coupled to a second pumping port and configured to block a gas  
flow through the second pumping port,

wherein the pumping cell is removed from the first pumping port and a substitute seal  
is provided to the first pumping port, the substitute seal being configured to block a gas flow  
through the first pumping port, and

wherein the seal is removed from the second pumping port and a substitute pumping  
cell is provided to the second pumping port such that a gas flow through the vacuum  
processing apparatus is reconfigured by providing the substitute seal to the first pumping port  
and providing the substitute pumping cell to the second pumping port

~~the at least one pumping cell can be removed from the first pumping port and coupled~~  
~~to a first different pumping port, and~~

~~the at least one seal can be removed from the second pumping port and coupled to a second different pumping port such that an arrangement of the at least one pumping cell and the at least one seal is reconfigured.~~

Claim 45 (Currently Amended): The vacuum processing apparatus according to claim 44, wherein the side wall ~~having~~ has a height of at most about four inches.

Claim 46 (Previously Presented): The vacuum processing apparatus according to claim 45, wherein the process chamber is made of a single unit of plate stock having a thickness of about four inches.

Claim 47 (Previously Presented): The vacuum processing apparatus according to claim 46, wherein the plate stock is aluminum.

Claim 48 (Previously Presented): The vacuum processing apparatus according to claim 45, wherein the plurality of pumping ports are located on the lower wall of the process chamber adjacent to a process chamber volume.

Claim 49 (Previously Presented): The vacuum processing apparatus according to claim 45, wherein three pumping ports are provided on the lower wall of the process chamber symmetrically spaced about a chuck assembly provided within the process chamber.

Claim 50 (Currently Amended): The vacuum processing apparatus according to claim 49, wherein

three pumping cells are connected to the process chamber, each one of the three pumping cells being connected to a respective one of the three pumping ports, and the three pumping ports being configured to receive said substitute seal in order to reconfigure the gas flow in the vacuum processing apparatus.

Claim 51 (Previously Presented): The vacuum processing apparatus according to claim 45, wherein two pumping ports are provided on the lower wall of the process chamber symmetrically spaced about a chuck assembly on opposing sides thereof.

Claim 52 (Currently Amended): The vacuum processing apparatus according to claim 51, wherein

two pumping cells are connected to the process chamber, each one of the two pumping cells being connected to a respective one of the two pumping ports, and the two pumping ports being configured to receive said substitute seal in order to reconfigure the gas flow in the vacuum processing apparatus.

Claim 53 (Previously Presented): The vacuum processing apparatus according to claim 44, further comprising means for reducing open volume within the process chamber.

Claim 54 (Previously Presented): The vacuum processing apparatus according to claim 53, wherein the means for reducing open volume comprises a chamber liner configured to displace open volume within the process chamber.

Claim 55 (Previously Presented): The vacuum processing apparatus according to claim 44, wherein the process chamber facilitates the formation of plasma.

Claim 56 (Currently Amended): A method of making an improved vacuum processing apparatus, comprising:

providing a processing chamber, including

a lower wall;

an upper wall;

a side wall coupled to the lower wall and the upper wall; and

a plurality of pumping ports, formed in one of the lower wall, the upper wall, or the side wall;

connecting ~~at least one~~ a pumping cell, integrally including a vacuum pump and a valve, to a first pumping port; ~~and~~

connecting ~~at least one~~ a seal to a second pumping port, ~~wherein~~ such that the seal blocks a gas flow through the second pumping port;

removing the pumping cell from the first pumping port and providing a substitute seal to the first pumping port such that the substitute seal blocks a gas flow through the first pumping port; and

removing the seal from the second pumping port and providing a substitute pumping cell to the second pumping port such that a gas flow through the vacuum processing apparatus is reconfigured by the providing the substitute seal to the first pumping port and the providing the substitute pumping cell to the second pumping port

~~the at least one pumping cell can be removed from the first pumping port and coupled to a first different pumping port, and~~

~~the at least one seal can be removed from the second pumping port and coupled to a second different pumping port such that an arrangement of the at least one pumping cell and the at least one seal is reconfigured.~~

Claim 57 (Previously Presented): The method according to claim 56, further comprising:

making the side wall with a height of at most about four inches.

Claim 58 (Previously Presented): The method according to claim 57, further comprising:

making the process chamber of plate stock with a thickness of about four inches.

Claim 59 (Previously Presented): The method according to claim 58, wherein the plate stock is aluminum.

Claim 60 (Previously Presented): The method according to claim 57, further comprising:

making the process chamber via a molding process.

Claim 61 (Previously Presented): The method according to claim 57, wherein said lower wall is a plate and said side wall is a rolled cylinder, and the making the process chamber includes welding the lower wall to the side wall.

Claim 62 (Previously Presented): The method according to claim 57, further comprising:

providing the plurality of pumping ports on the lower wall of the process chamber adjacent to a process chamber volume.

Claim 63 (Previously Presented): The method according to claim 57, further comprising:

providing a chuck assembly in the process chamber; and  
providing three pumping ports on the lower wall of the process chamber  
symmetrically spaced about the chuck assembly.

Claim 64 (Currently Amended): The method according to claim 63, further comprising:

connecting three pumping cells to the process chamber,  
wherein each one of the three pumping cells are connected to a respective one of the  
three pumping ports and the three pumping ports being configured to receive said substitute  
seal in order to reconfigure the gas flow in the vacuum processing apparatus.

Claim 65 (Previously Presented): The method according to claim 57, further comprising:

providing a chuck assembly in the process chamber; and  
providing two pumping ports on the lower wall of the process chamber symmetrically  
spaced about the chuck assembly on opposing sides thereof.

Claim 66 (Currently Amended): The method according to claim 65, further comprising:

connecting two pumping cells to the process chamber,  
wherein each one of the two pumping cells are connected to a respective one of the  
two pumping ports and the two pumping ports being configured to receive said substitute seal  
in order to reconfigure the gas flow in the vacuum processing apparatus.

Claim 67 (Previously Presented): The method according to claim 56, further comprising:

providing a chamber liner in the process chamber configured to displace open volume within the process chamber.

Claim 68 (Previously Presented): The method according to claim 56, further comprising:

providing an upper electrode to facilitate the formation of plasma in the process chamber.

Claim 69 (New): The method according to claim 56, wherein  
the substitute seal provided to the first pumping port is the seal removed from the second pumping port, and

the substitute pumping cell provided to the second pumping port is the pumping cell removed from the first pumping port.